

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	14	polysilicon and silicide and "low region" and rate and (CMP or "chemical mechanical polishing").clm"	US-PGPUB	OR	ON	2006/08/28 07:42
L3	3	polysilicon and silicide and "low region" and rate and (CMP or "chemical mechanical polishing").clm.	US-PGPUB	OR	ON	2006/08/28 07:44
L5	2	"6743683".pn.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/28 07:48
L6	1339	((438/626) or (438/630) or (438/691)).CCLS.	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/08/28 07:48
L7	0	("barns-chris-e.in.").PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/08/28 07:50
L8	15	barns-chris-e.in.	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/08/28 07:50
L9	14	doczy-mark.in.	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/08/28 07:50